



**UNIVERSITY**  
*of*  
**GLASGOW**

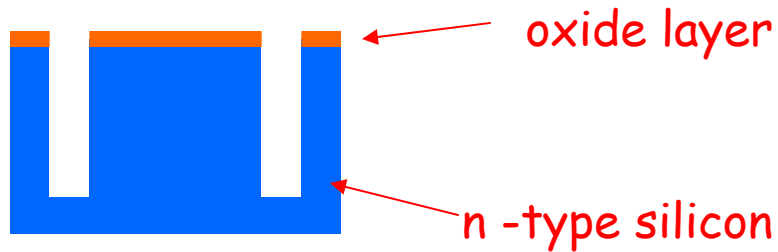
# Update of 3D activity at the University of Glasgow

R. Bates, V. O'Shea, C. Parkes,  
V. Wright, A. Blue

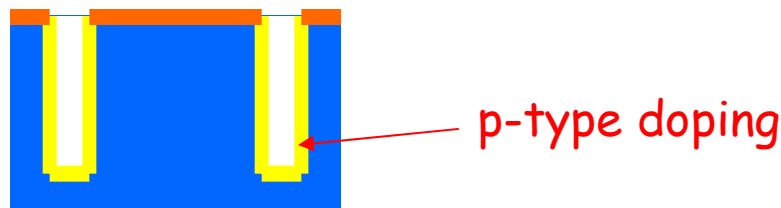
# Contents

- Latest device formation
- Irradiation tests
- Strip and pixel detectors
- Bit of fun: Spectra from GaAs 3D device

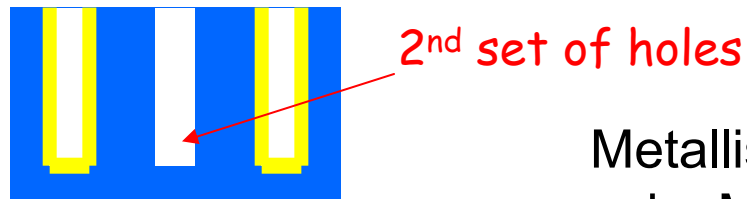
# Fabrication



1<sup>st</sup> set of holes DRIE  
or Electro-chemical etching



p-type doping  
Boron diffusion  
at 1030°C for 10min



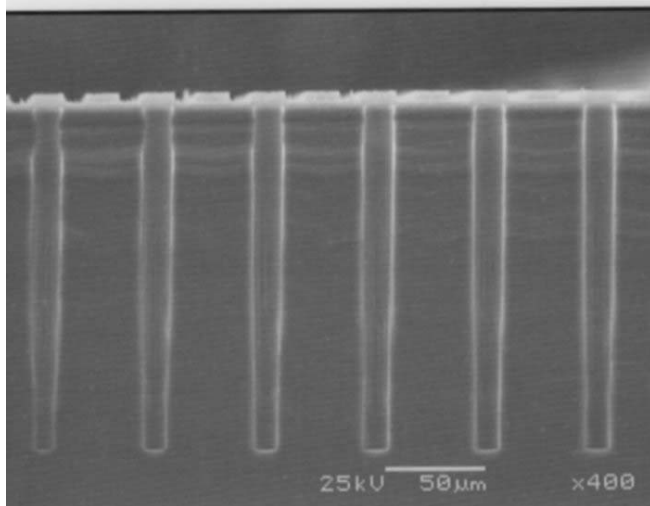
Etch of 2<sup>nd</sup> set of holes  
Metallise, Ru, by atomic layer deposition  
by Metorex to form electrical contact

Metallisation of top surface to form device type (pixel, strip)

# Two methods to form pores

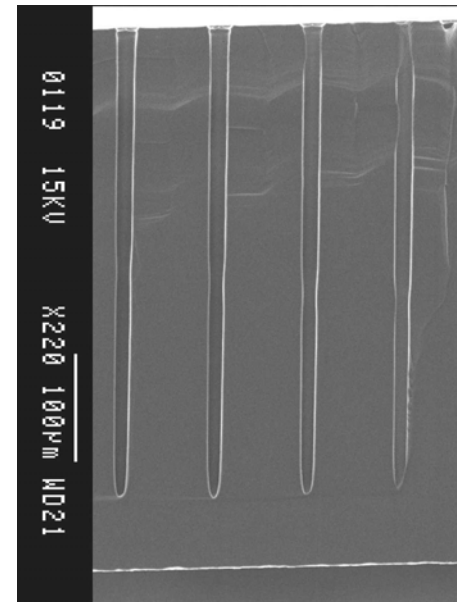
## DRIE

- So far, maximum aspect ratio: 18:1 (depth 183 $\mu\text{m}$ )
- Modification to standard equipment to obtain deep narrow parallel walled pores
- In conjunction with STS



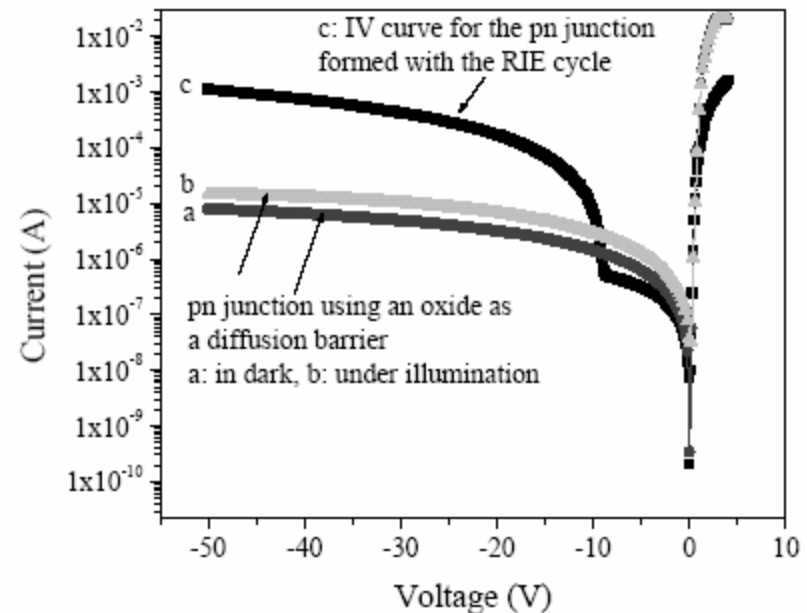
## Electro-chemical etching

- maximum aspect ratio: 30:1 (depth 440  $\mu\text{m}$ ,  $\Phi=14$   $\mu\text{m}$ )
- 24 hours per wafer
- Cheap



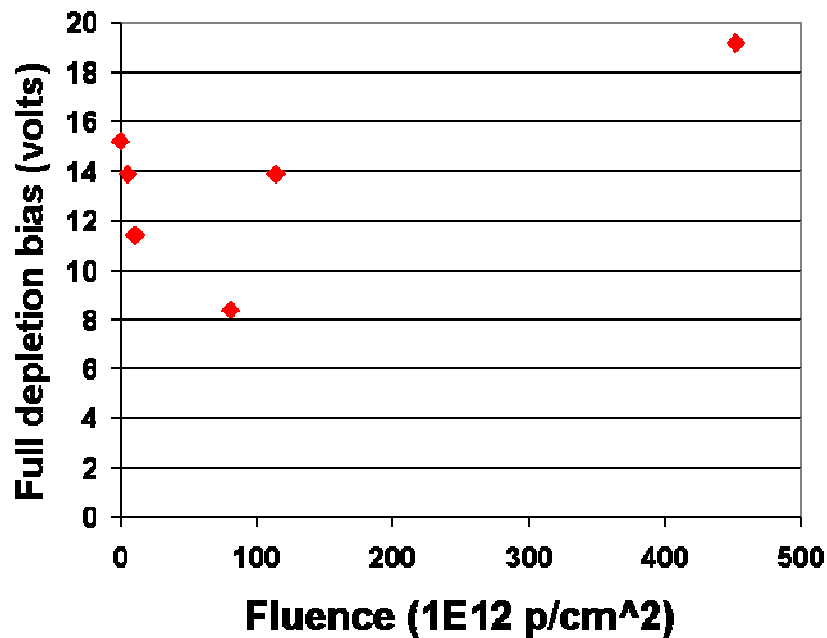
# IV of devices

- Good rectifying np junction formed
- Oxide as diffusing barrier isolates individual cells
- RIE removal of top surface caused increase in current after -10V



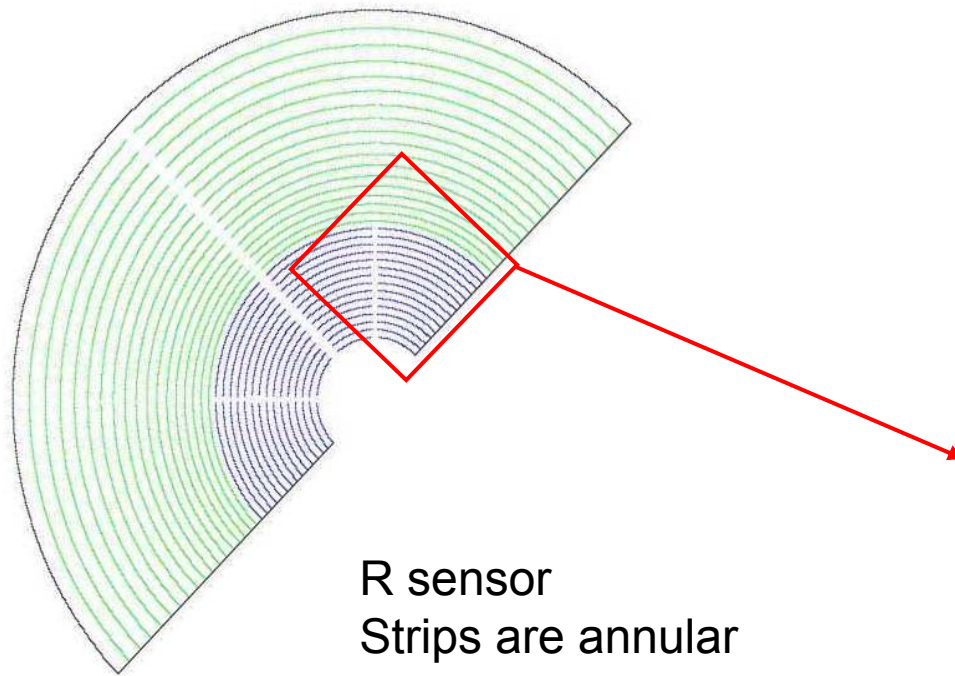
# Proton irradiation

- High res n-type silicon, 85 $\mu$ m pitch, close-packed hexagonal pixels
- Irradiation with 24 GeV/c protons at CERN
- 7 fluences from  $5 \times 10^{12}$  to  $4.5 \times 10^{14}$  p /cm<sup>2</sup>



For  $4.5 \times 10^{14}$  p/cm<sup>2</sup>  
Depletion voltage = 19V  
Type inversion observed

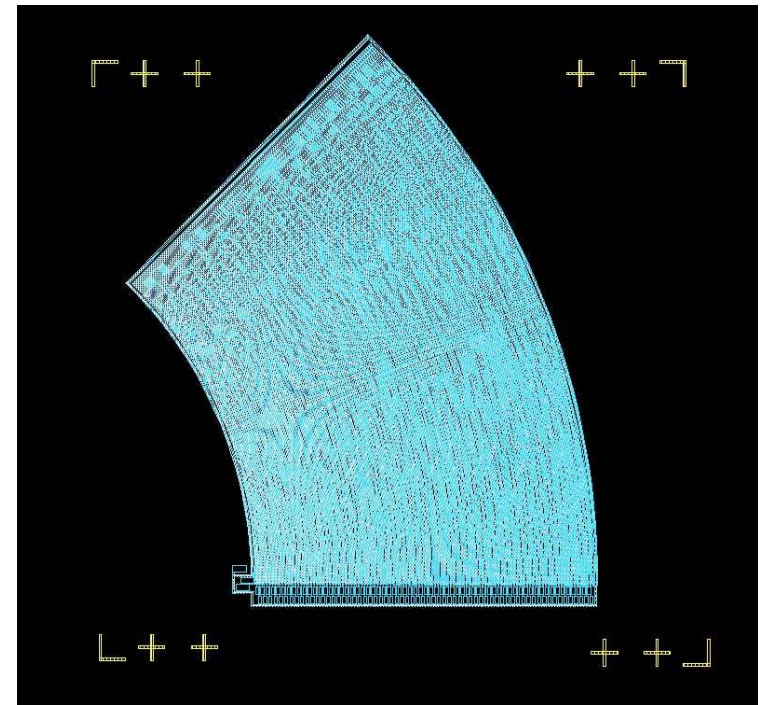
# 3D strip detectors : VELO design



R sensor  
Strips are annular  
 $\pi/4$  segments  
 $R = 8\text{mm}$  to  $R = 42\text{mm}$   
512 strips

3D device

Pitch varies linearly from  $45\mu\text{m}$  at the innermost region to  $90\mu\text{m}$  at strip 128.



# LHCb VELO

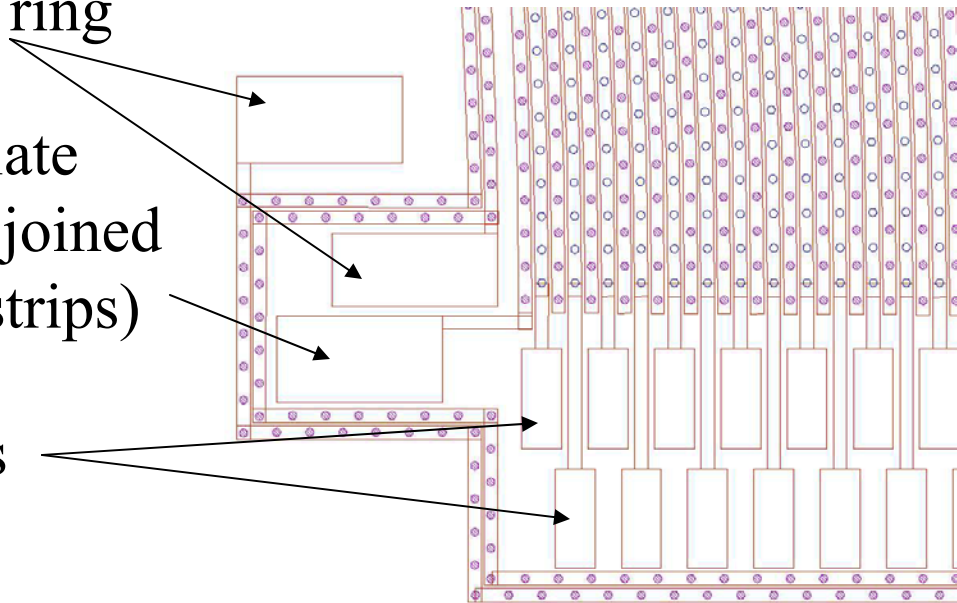
Constant pore spacing of  $50\mu\text{m}$  along the strip.

Pore spacing varies with radius.

Bond pads for guard ring

Bond pad for intermediate  
n-type strips (these are joined  
at the other end of the strips)

Readout bond pads  
rectifying contacts



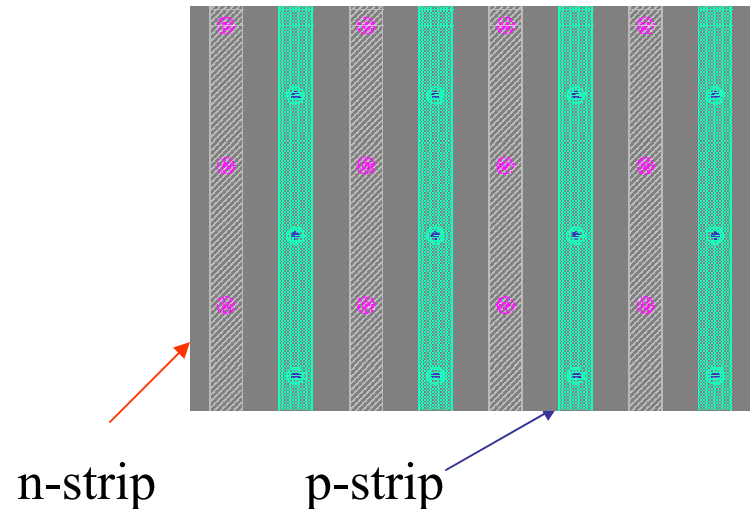
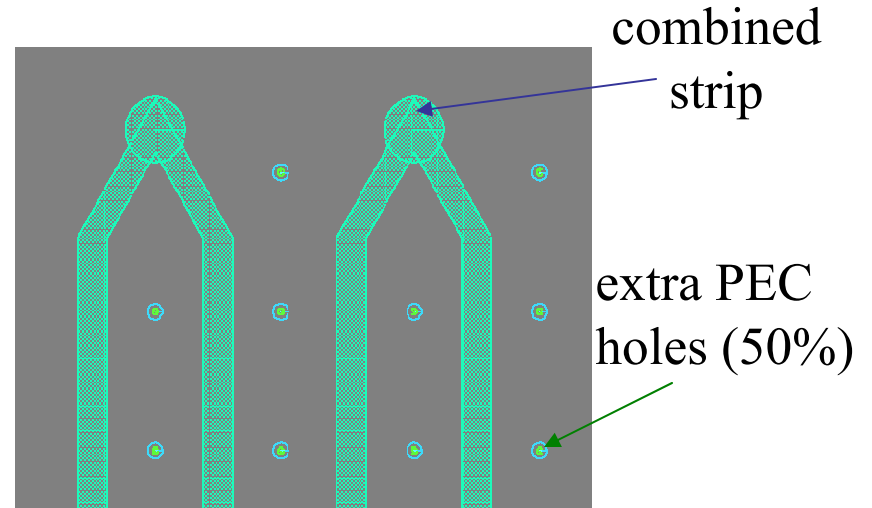
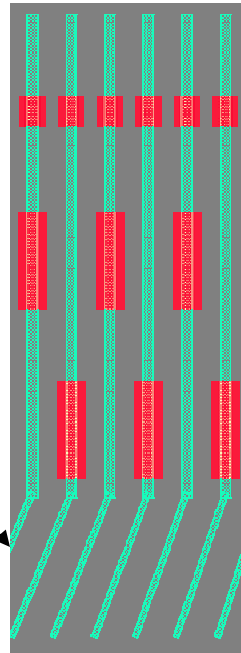


# ATLAS SCT

- Baby barrel detector
- 1cm long strips
- Readout strips: 128 + 2 at 80  $\mu\text{m}$  pitch
- Fan-out to bondpads: 85  $\mu\text{m}$  pitch
- Pores: 2 or 5  $\mu\text{m}$  diameter  
42.5  $\mu\text{m}$  pitch n to n  
30  $\mu\text{m}$  pitch n to p

bond pads

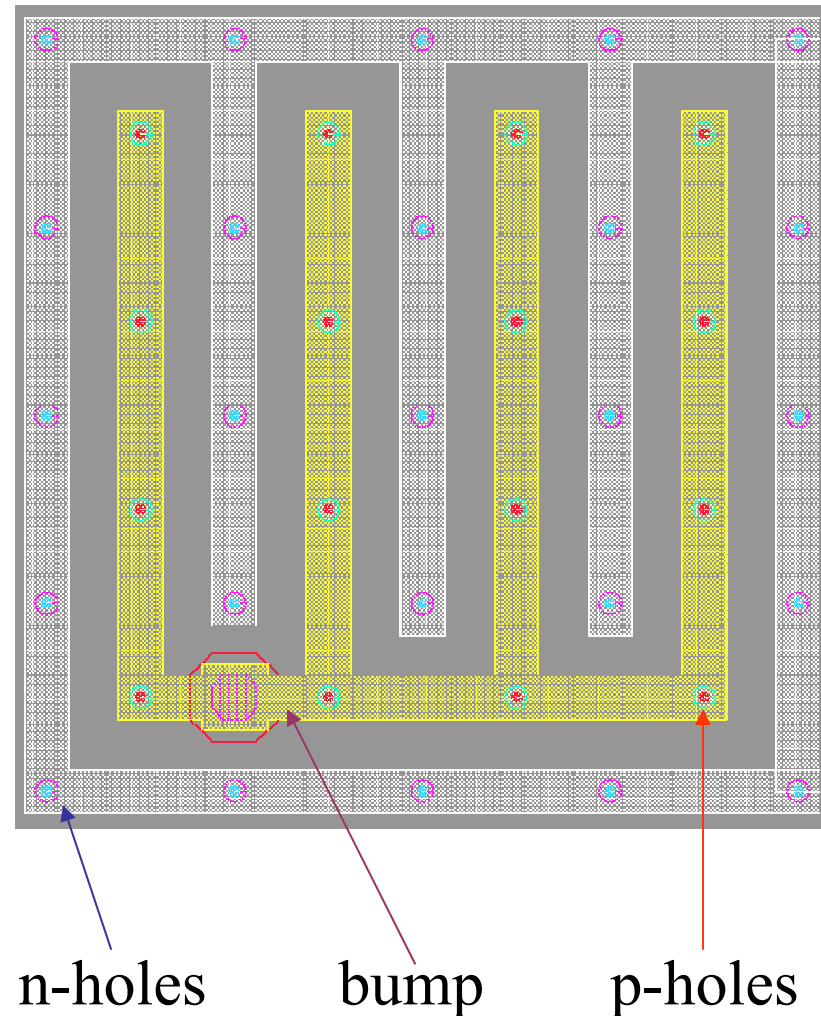
fanning



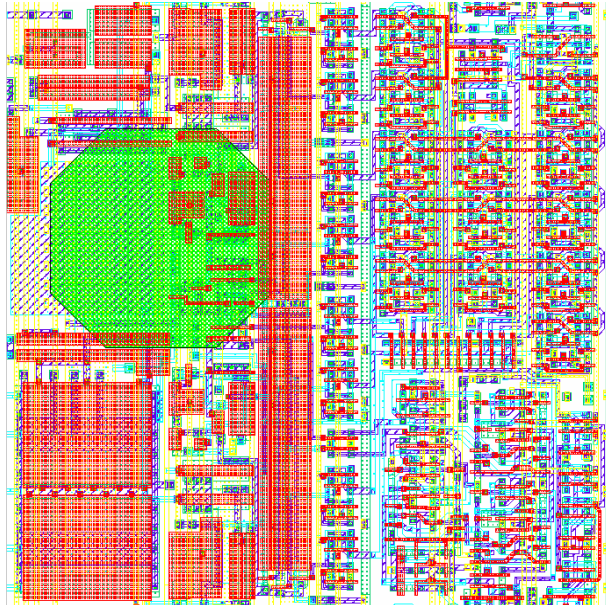
# 3D pixel detector : Medipix1

- Pixels: 64 x 64 array  
170 x 170  $\mu\text{m}^2$
- Strips: 42.5  $\mu\text{m}$  pitch
- Pores: 2 or 5  $\mu\text{m}$  diameter  
42.5  $\mu\text{m}$  pitch (n-n)  
30.0  $\mu\text{m}$  pitch (n-p)

Same structure of holes as  
ATLAS SCT  
Metal layers differ to realize  
different detector type



# Medipix 1

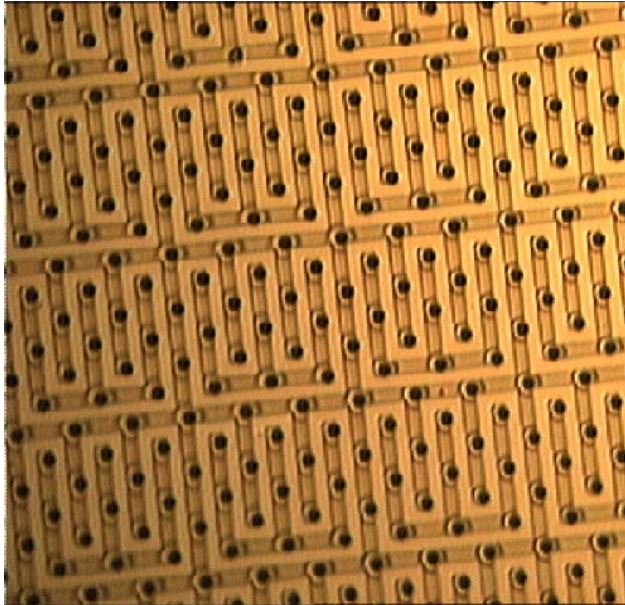


Single photon counting chip  
Counter in each pixel  
64 x 64 pixels  
170  $\mu\text{m}$  pixel pitch

3D detectors  
Reduce charged sharing between  
adjacent pixels particularly  
useful for photon counting

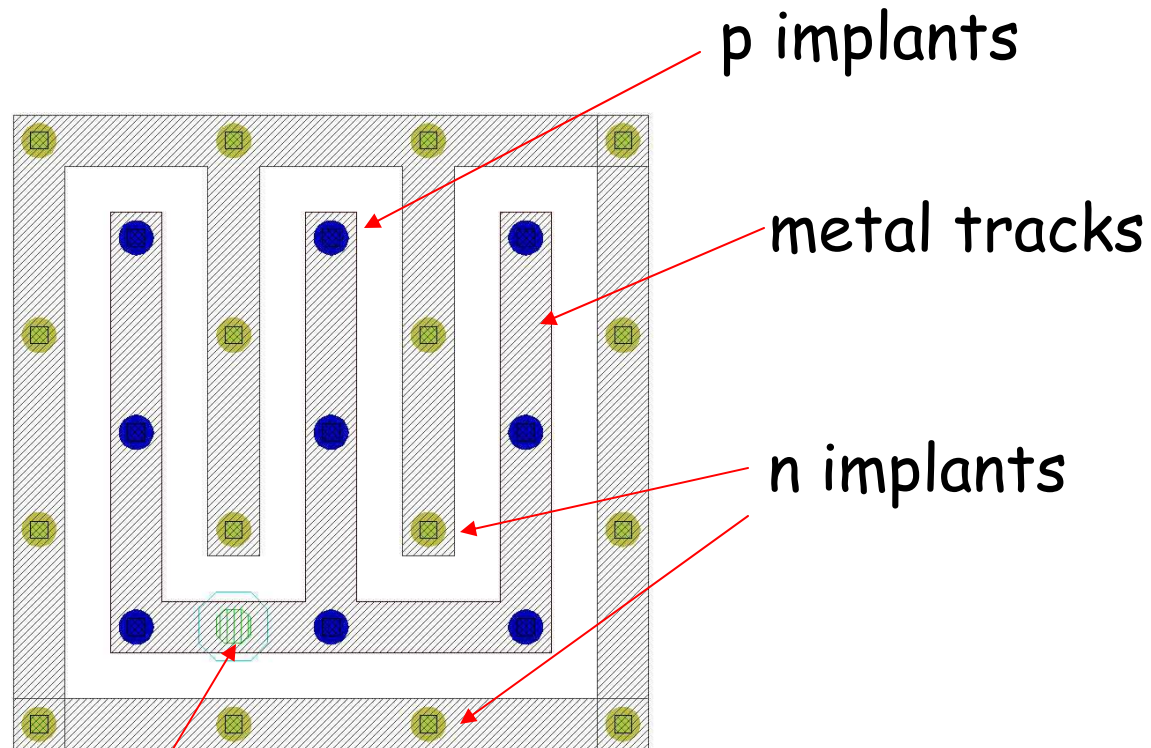
Planar detectors  
Small pixels with thick sensors  
Result in charge sharing  
Up to 20% for 20keV, 55  $\mu\text{m}$  pixel 300  $\mu\text{m}$  thick detector

# 1<sup>st</sup> Medipix design



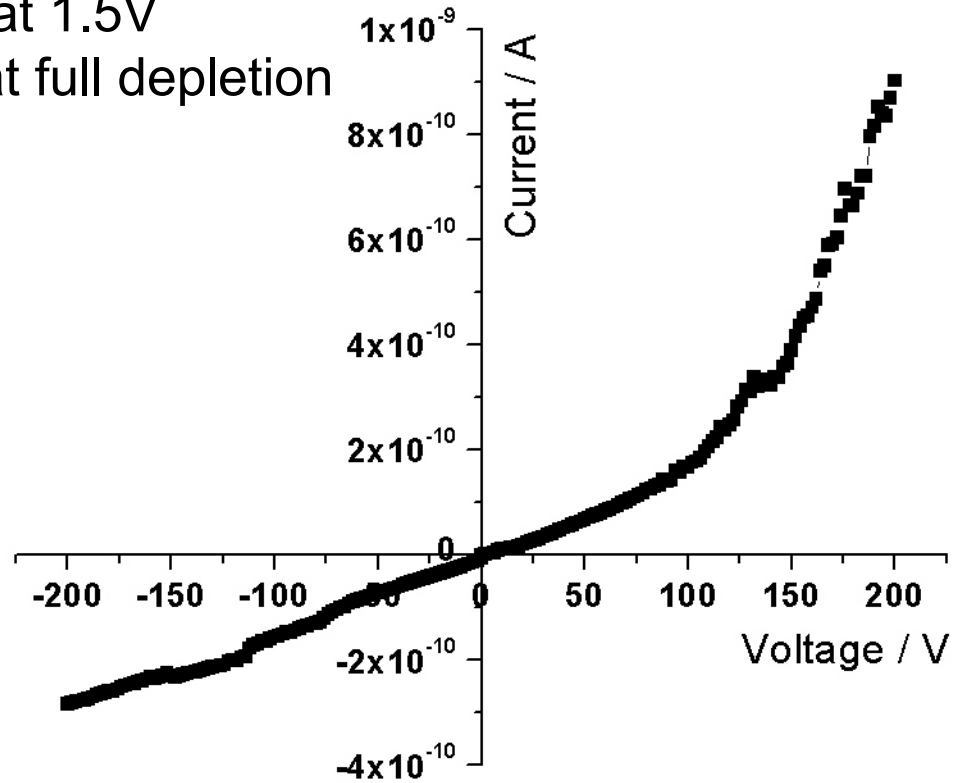
pore diameter :  $10\mu\text{m}$   
width of metal strips :  $15\mu\text{m}$   
pitch :  $57\mu\text{m}$   
cell pitch :  $170\mu\text{m}$

position of "bump" consistent with Medipix1 chip



# IV of single pixel

Full depletion at 1.5V  
Current  $\sim$  pA at full depletion

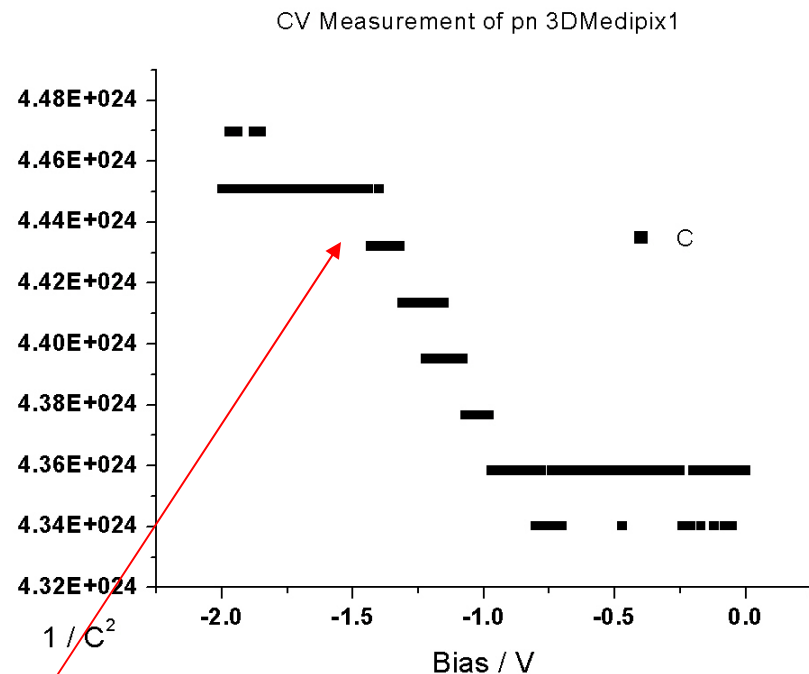


# CV for single pixel

Capacitance of 500fF at full depletion  
Note 3D pixel is self guarded

Planar diode = 10fF  
Calculated Coaxial approx = 800fF

From this data expect  
6cm strip ~ 70pF (~ 12pF/cm)  
Typical strip detector ~ 1pF/cm

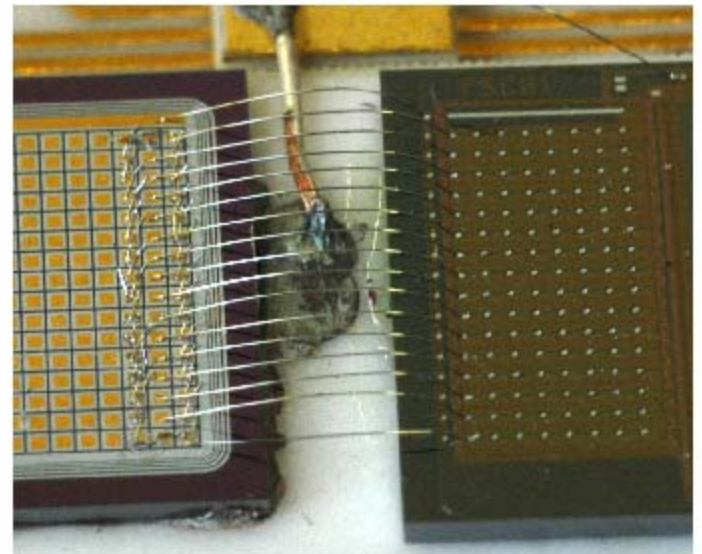
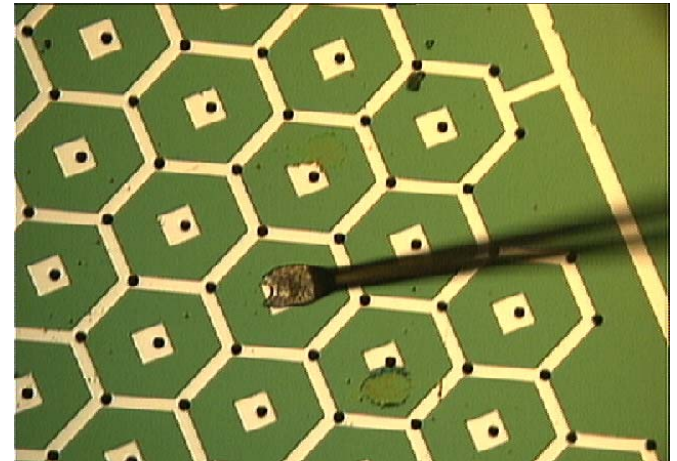


Full depletion ~1.5V

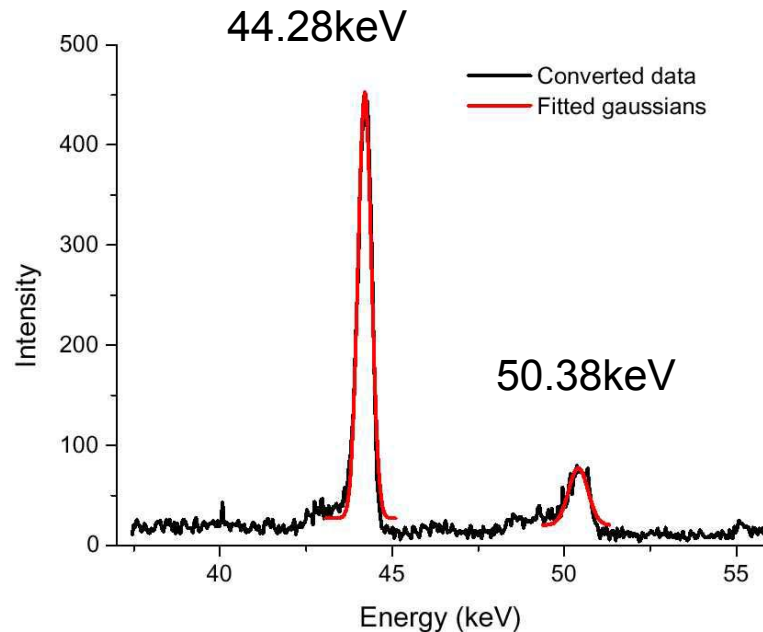


# 3D GaAs diode

- r/o Dash-E : RAL photon counting spectroscopic pixel detector
- SI U-LEC GaAs 500  $\mu\text{m}$  thick
- 170  $\mu\text{m}$  pitch 3D hexagonal pixel
- Laser drilled holes,  $\Phi = 10\ \mu\text{m}$
- Metal Schottky contacts
- Wire bonded NOT bump bonded
- Full depletion at 4V, operated at 10V
- Current = 5nA at 20C, operated at -30C, 10 pA



# Results for Terbium $K_{\alpha}$ and $K_{\beta}$



CCE 100%

FWHM = 467 eV = 1.06%

$\sigma = 199$  eV

Large noise due to wire bond

$\sigma_{\text{electronics}} = 137$  eV

Fano factor calculated = 0.112

Theoretical value = 0.1

Assume  $\varepsilon = 4.2$  eV

2D silicon (300 $\mu$ m) bump bonded (20C)	1.32 %
2D silicon (300 $\mu$ m) wire bonded (20C)	2.21 %
3D GaAs (500 $\mu$ m) wire bonded (-30C)	1.06%